## IN THE CLAIMS

1. (currently amended): A semiconductor device comprising:

a semiconductor chip having a first main surface on which a plurality of electrode pads are provided, a second main surface which opposes said first main surface, and a plurality of side surfaces positioned between said first main surface and said second main surface;

an extension portion formed in contact with said side surfaces of said semiconductor chip so as to surround said semiconductor chip;

an insulating film formed on a surface of said extension portion and said first main surface such that a part of each of said electrode pads is exposed;

a plurality of wiring patterns formed on said insulating film so as to be electrically connected to said electrode pads, respectively and extended from said electrode pads to the surface of <u>said insulating film on</u> said extension portion;

a sealing portion formed on said wiring patterns and said insulating film such that a part of said wiring patterns is exposed; and

a plurality of external terminals provided over said wiring patterns in a region including the upper side of said extension portion;

wherein the electrode pads are arranged in a first line extending in a first direction along a peripheral edge of the semiconductor chip on the first main surface, and the external terminals are arranged in a second line extending in a second direction perpendicular to said first direction, and are electrically connected to the electrode pads in a one-on-one connection relationship.

- 2. (original): The semiconductor device according to claim 1, further comprising a plurality of electrode posts formed between said wiring patterns and said external terminals, wherein said sealing portion is formed such that the top surface of said electrode posts is exposed.
- 3. (original): The semiconductor device according to claim 1, wherein said electrode posts are formed from a conductive material.

**AMENDMENT** 

- 4. (currently amended): The semiconductor device according to claim 3, wherein a thin oxidation layer is formed on a <u>side</u> surface of said electrode posts.
- 5. (original): The semiconductor device according to claim 1, wherein said external terminals are formed as solder balls.
- 6. (original): The semiconductor device according to claim 1, wherein said external terminals are lands.
- 7. (currently amended): The semiconductor device according to claim 1, wherein a portion of said wiring patterns on a boundary and a vicinity of a boundary between a region on the upper side of said semiconductor chip and said extension portion is formed wider or more thickly than other portions of said wiring patterns.
- 8. (original): The semiconductor device according to claim 1, wherein said extension portion is formed from a material having a greater molding shrinkage than the molding shrinkage of said sealing portion.
- 9. (original): The semiconductor device according to claim 8, wherein said extension portion is formed from a liquid resin having a linear expansion coefficient in a lower temperature range than glass transition temperature of less than 1.5 x 10.5/°C and a modulus of elasticity within a range of 7.8 to 22 GPa.
  - 10. (currently amended): The semiconductor device according to claim 1. comprising: A semiconductor device comprising:
- a semiconductor chip having a first main surface on which a plurality of electrode pads is provided, a second main surface which opposes said first main surface, and a plurality of side surfaces positioned between said first main surface and said second main surface;

10/697,311

an extension portion formed in contact with said side surfaces of said semiconductor chip;

a passive element comprising connection terminals and provided on said extension portion; wherein

[[an]] the insulating is film formed on a surface of said extension portion and said first main surface such that a part of each of said electrode pads and a part of said connection terminals [[are]] is exposed. [[;]]

a plurality of wiring patterns electrically connected to said electrode pads, respectively and extended from said electrode pads to the surface of said extension portion;

a scaling portion formed on said wiring patterns and said insulating film such that a part of said wiring patterns is exposed; and

a plurality of external terminals provided over said wiring patterns in a region including the upper side of said extension portion.

- 11. (currently amended): The semiconductor device according to claim 10, wherein a portion of said wiring patterns on a boundary and a vicinity thereof between a region on the upper side of said semiconductor chip and said extension portion is formed wider or more thickly than other portions of said wiring patterns.
- 12. (withdrawn): The semiconductor device according to claim 10, wherein said passive element provided on said extension portion comprises a plurality of connection terminals, one of said connection terminals being connected to said electrode pads and the other connection terminal being connected to said external terminals.
- 13. (withdrawn): The semiconductor device according to claim 10, wherein said passive element provided on said extension portion comprises a plurality of connection terminals, one of said connection terminals being connected to a specific external terminal and the other connection terminal being connected to a different external terminal.

AMENDMENT 4 . 10/697,311

- 14. (withdrawn): The semiconductor device according to claim 10, further comprising a plurality of electrode posts formed between said wiring patterns and said external terminals, wherein said sealing portion is formed such that the top surface of said electrode posts is exposed.
- 15. (withdrawn): The semiconductor device according to claim 10, wherein said electrode posts are formed from a conductive material.
- 16. (currently amended): The semiconductor device according to claim 10, wherein a thin oxidation layer is formed on a side surface of said electrode posts.
- 17. (withdrawn): The semiconductor device according to claim 10, wherein said external terminals are solder balls.
- 18. (withdrawn): The semiconductor device according to claim 10, wherein said external terminals are lands.
- 19. (withdrawn): The semiconductor device according to claim 10, wherein said extension portion is formed from a material having a greater molding shrinkage than the molding shrinkage of said sealing portion.
- 20. (withdrawn): The semiconductor device according to claim 19, wherein said extension portion is formed from a liquid resin having a linear expansion coefficient in a lower temperature range than glass transition temperature of less than 1.5 x 10<sup>-5</sup>/°C and a modulus of elasticity within a range of 7.8 to 22 GPa.

10/697,311